

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION: Eiji YONEDA, et al.

SERIAL NUMBER: 10/743,809

FILED: December 24, 2003

FOR: ONIUM SALT COMPOUND AND RADIATION-SENSITIVE RESIN COMPOSITION
INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. 1.97

Assistant Commissioner for Patents
 PO BOX 1450
 ALEXANDRIA, VA 22313-1450

Sir:

Applicant(s) wish(es) to disclose the following information.

REFERENCES

Applicant(s) wish(es) to make of record the documents listed on the attached Form PTO-1449. Copies of the listed documents are attached, where required, as are either statements of relevancy or any readily available full or partial English translations of any non-English-language documents.

RELATED CASES

Attached is a list of Applicant's(s') pending applications and issued patents which may be related to the present application. Copies of the documents, where required, are attached along with Form PTO-1449.

CERTIFICATION

The undersigned certifies that

each item of information contained in this Information Disclosure Statement was cited in a communication from a foreign or international patent office in a counterpart foreign or international application for the first time (to the knowledge of the undersigned, having made reasonable inquiry) not more than three months prior to the filing of this statement.

no item of information contained in this Information Disclosure Statement was cited in a communication from a foreign or international patent office in a counterpart foreign or international application or, to the knowledge of the undersigned, having made reasonable inquiry, was known to any individual designated in 37 C.F.R. 1.56(c) more than three months prior to the filing of this statement.

BASIS FOR CONSIDERATION

This Information Disclosure Statement is filed:

without fee and within three months of the filing date of the application.

without fee and within three months of the date of entry of the U.S. national stage.

without fee and before the mailing date of a first Office Action on the merits (to the knowledge of the undersigned).

without fee and with the appropriate certification above.

without fee and with a new CPA application.

without fee and with a Request for Continued Examination.

with fee and before the mailing date of any Final Office Action, Notice of Allowance or an action that otherwise closes prosecution (to the knowledge of the undersigned).

with fee, appropriate certification above, and before payment of the Issue Fee.

DEPOSIT ACCOUNT

Please charge any additional fees for the papers being filed herewith and for which no check is enclosed herewith, or credit any overpayment to Deposit Account No. 50-1442.

Respectfully submitted,

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DOCKET NO. 588-058-27

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Eiji YONEDA, et al.

ART UNIT:

SERIAL NO.: 10/743,809

EXAMINER:

FILING DATE: December 24, 2003

FOR: ONIUM SALT COMPOUND AND RADIATION-SENSITIVE RESIN
COMPOSITION

STATEMENT OF RELEVANCY

ASSISTANT COMMISSIONER FOR PATENTS

PO BOX 1450

ALEXANDRIA, VA 22313-1450

SIR:

This Statement of Relevancy is herewith submitted with the concurrently filed
Information Disclosure Statement.

Japanese Patent Application Laid-open No. 59-45439 discloses a chemically-amplified
radiation-sensitive composition containing a polymer of which the carboxyl group or phenolic
hydroxyl group is protected with a t-butoxycarbonyl group and a photoacid generator. This
composition utilizes the effect of the polymer to release the t-butoxycarbonyl group by the action
of an acid generated by exposure to form an acidic functional group such as a carboxylic group or
a phenolic hydroxyl group, which renders an exposed area on a resist film readily soluble in an
alkaline developer.

Japanese Patent Application Laid-open No. 63-36332 discloses a sulfonium salt
compound having a sulfonyl structure bonded with an aromatic ring which is useful as a
photoinitiator due to a cation mechanism.

Consideration of the above cited references with all Information Disclosure Materials concurrently filed is respectfully requested.

Respectfully submitted,

PIPER RUDNICK LLP



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Form PTO 1449 (Modified)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	DOCKET NO.	SERIAL NO.
		5988-058-27	10/743,809
LIST OF REFERENCES CITED BY APPLICANT (Use Several Sheets if Necessary)		APPLICANT	
		Eiji YONEDA, et al.	
		FILING DATE	GROUP ART UNIT
		December 24, 2003	

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES	NO
	AK	JP59-45439	3/14/1984	JAPAN		X
	AL	JP63-36332	2/17/1988	JAPAN		X
	AM					

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

AN	Crivello, et al., "Complex Triarylsulfonium Salt Photoinitiators. II. The Preparation of Several New Complex Triarylsulfonium Salts and the Influence of Their Structure in Photoinitiated Cationic Polymerization", Journal of Polymer Science, Vol. 18, pp. 2697-2714, 1980.
AO	Hattori, et al., "Successive Beckmann Rearrangement-Alkylation Sequence by Organoaluminum Reagents. A Simple Route to <i>dl</i> -Pumiliotoxin C", J. Am. Chem. Soc., Vol. 103, pp. 7368-7370, 1981.
AP	Alemagna, et al., "S _N Ar Nucleophilic Substitutions of Cr(CO) ₅ -Complexed Aryl Halides with Thiolates under Phase-Transfer Conditions", J. Org. Chem., Vol. 48, pp. 605-607, 1983.
AQ	Migita, et al., "The Palladium Catalyzed Nucleophilic Substitution of Aryl Halides by Thiolate Anions", Bull. Chem. Soc. Jpn., Vol. 53, pp. 1385-1389, 1980.

EXAMINER	DATE CONSIDERED
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*EXAMINER: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.